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이산화탄소의 초임계 상거동

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Cloud points of amine compound with fluoride group surfactant in high pressure carbon dioxide have been investigated. These cloud points was used as basic factor for supercritical CO₂ resist removal (SCORR) process. Amine compound and fluoride group surfactant was used as additives, because amine compound was used to clean wafer pattern. And mixture of amine compound and carbon dioxide can form transparent homogeneous phase by fluoride group surfactant. The cloud points were measured using a high pressure variable-volume view cell. All systems exhibited a lower critical solution temperature (LCST) phase behavior. This experiment was performed in the range of 313.2 to 353.2 K.